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	Туре	L#	Hits	Search Text	DBs	Time Stamp	Commen ts
9	BRS	L47	113	(photoresist or photo-resist or (photo adj resist)) near10 poison\$4	USPA T; US-PG PUB; EPO; JPO; DERW ENT; IBM_T DB	2003/06/16 14:38	
10	BRS	L54	161	(low-k or (low near3 (dielectric or k or constant))) near20 (poison\$4 or (chemical adj inert) or chemical-inert or inactive or non-react\$4)	USPA T; US-PG PUB; EPO; JPO; DERW ENT; IBM_T DB	2003/06/16 14:42	
11	BRS	L61	22	47 and 54	USPA T; US-PG PUB; EPO; JPO; DERW ENT; IBM_T DB	2003/06/16 14:42	

	Туре	L#	Hits	Search Text	DBs	Time Stamp	Commen ts
1	BRS	L1	10132	(photoresist or photo-resist or (photo adj resist) or low-k or (low near3 (dielectric or k or constant))) near20 (poison\$4 or (chemical adj inert) or chemical-inert or inactive or non-react\$4 or react\$4)	US-PG PUB; EPO;	2003/06/16 14:03	
2	BRS	L8	7197	dual-damascene or damascene or dualdamascene	USPA T; US-PG PUB; EPO; JPO; DERW ENT; IBM_T DB	2003/06/16 14:03	
3	BRS	L15	613	1 and 8	i	2003/06/16 14:03	